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Sommario/riassunto

This revised and up-to-date translation of the very successful German original accompanies the reader from the introductory level right up to in-depth knowledge, backed by numerous literature references. It begins with the most important fundamentals of microtechnology and chemistry on which an understanding of shaping nanoscale structures is based. It then goes on to describe a variety of examples to illustrate the fabrication of nanostructures from different materials, before presenting readers with a wide range of methods for characterization of the generated structures. Thanks to i
